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Docket No.: T0203.0008/P008  
(PATENT)

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re Patent Application of:  
Seitaro Matsuo et al.

Application No.: 10/510,479

Confirmation No.: 7443

Filed: October 8, 2004

Art Unit: 1763

For: ECR PLASMA SOURCE AND ECR  
PLASMA DEVICE

Examiner: R. K. Dhingra

**AMENDMENT IN RESPONSE TO NON-FINAL OFFICE ACTION**

MS Amendment  
Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Dear Sir:

**INTRODUCTORY COMMENTS**

In response to the Office Action dated July 14, 2006, please amend the above-identified U.S. patent application as follows:

**Amendments to the Claims** are reflected in the listing of claims which begins on page 2 of this paper.

**Remarks/Arguments** begin on page 6 of this paper.